

INTEGRATED VERTICAL SPIRAL INDUCTOR ON SEMICONDUCTOR
MATERIAL

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ABSTRACT

A new structure is provided for the creation of an inductor on the surface of a silicon semiconductor substrate. The inductor is of spiral design and
10 perpendicular to the plane of the underlying substrate. Conductor line width can be selected as narrow or wide, ferromagnetic material can be used to fill the spaces between the conductors of the spiral inductor. The spiral inductor of the invention can further by used in series or
15 in series with conventional horizontal inductors.

Fig. 1 is suggested for publication.

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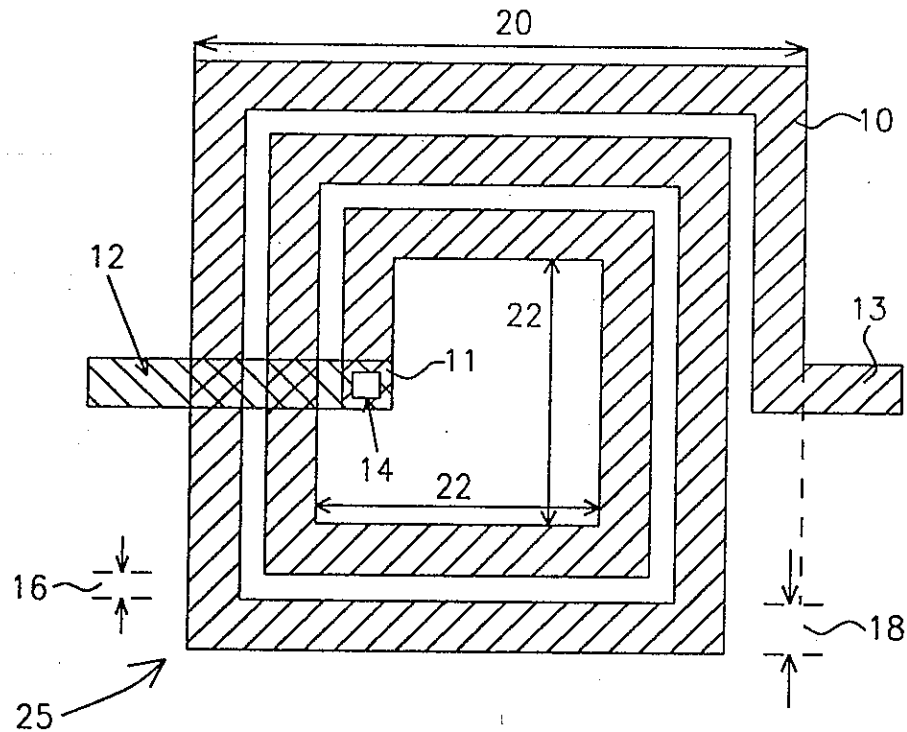


FIG. 1

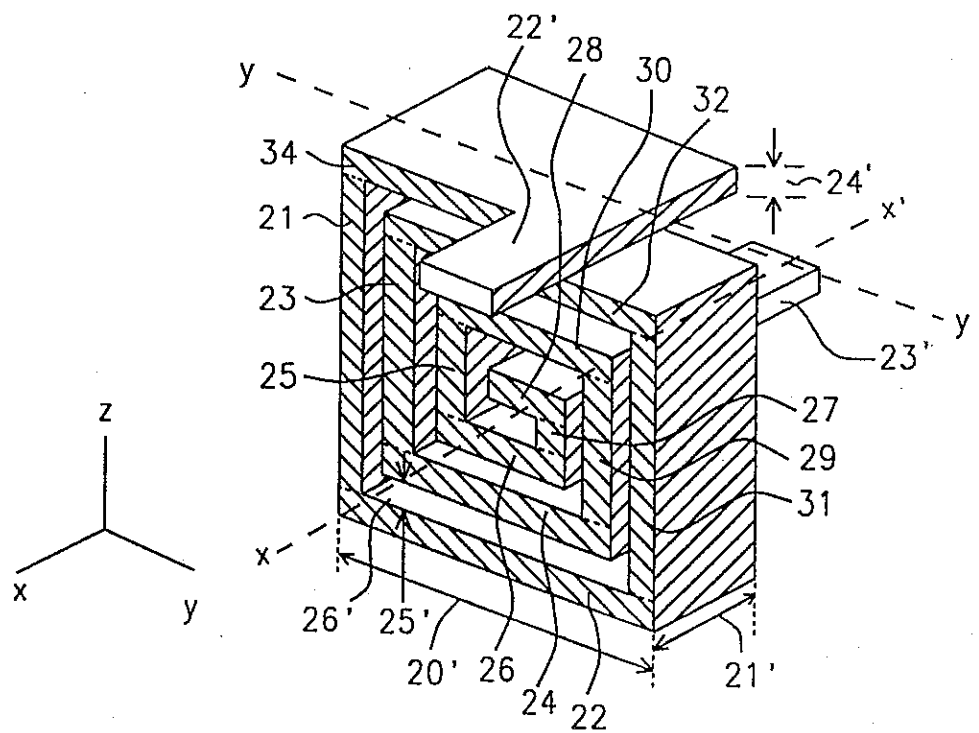


FIG. 2a